



CONTENTS

Contents

<u>SUBJECT</u>	<u>PAGE</u>
Acknowledgement	i
Abstract	ii
CHAPTER I	
BASIC FOUNDATION	
1.1 INTRODUCTION	1
1.2 PLASMA CONDITIONS	1
1.3 PLASMA TYPES	3
1.3.1 Cold Plasma	3
1.3.2 Thermal Plasma	3
1.4 COAXIAL DISCHARGE	4
1.4.1 Plasma Focus	4
1.4.2 Plasma Coaxial Gun	6
1.5 PLASMA DEPOSITION	8
1.6 SURVEY OF PREVIOUS WORK	11
1.7 THE AIM OF THE WORK	15

CHAPTER II

EXPERIMENTAL ARRANGEMENT

2.1 INTRODUCTION	16
2.2 THE VACUUM SYSTEM	17
2.3 THE CAPACITOR BANK AND POWER SUPPLY	17
2.4 THE TRIGGERING SYSTEM	18
2.5 PLASMA COAXIAL TUBE	20
2.6 SAFETY ARRANGEMENTS	22
2.6.1 The Dumping System	22
2.6.2 The Earthing Rod	24
2.7 SUMMARY	25

CHAPTER III

DIAGNOSTIC TECHNIQUES

3.1 INTRODUCTION	26
3.2 ELECTRICAL PARAMETERS	26
3.2.1 Current Measurement with Rogowsky Coil	27
3.2.2 Voltage Measurement by Capacitive Coupling Potential Divider	30
3.3 SHEATH DYNAMICS	32
3.3.1 Pick-up Loops for Measuring the Sheath Dynamics	32
3.3.2 Magnetic Probes for Measuring the Sheath Velocity	33

4.6 ENERGY CALCULATIONS	71
4.6.1 Source Energy	71
4.6.2 Deposited Energy	71
4.6.3 Kinetic Energy	71
4.6.4 Internal Energy	72
4.6.5 Kinetic Efficiency	73
4.6.6 Internal Efficiency	73
4.6.7 Total Efficiency	73
4.7 THEORETICAL ANALYSIS	74
4.8 CONCLUSION	80

CHAPTER V

DEPOSITED THIN FILM ANALYSIS

5.1 INTRODUCTION	81
5.2 SEM ANALYSIS	82
5.3 DEPOSITED MATERIAL THICKNESS	87
5.3.1 Interferometry for Thickness Measurements	87
5.3.2 Microdensitometer for Relative Thickness Measurement	89
5.4 CONCLUSION	93

CHAPTER VI

CONCLUSION	94
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REFERENCES

ARABIC SUMMARY